

<b>Notic of Referenc s Cited</b>	Application/Control No. 09/966,958		Applicant(s)/Patent Under Reexamination LU ET AL.	
	Examiner Sin J Lee		Art Unit 1752	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,691,101	11-1997	Ushirogouchi et al.	430/176
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Kanda et al., "Advanced Microlithography Process with Chemical Shrink Technology", Advances in Resist Technology and PProcessing XVII, vol.3999 (2000), pg.881-889.
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.